

Nanosecond-laser conditioning of multilayer dielectric gratings for picosecond-petawatt laser systems

Kun Shuai^{1,2,3}, Yuanan Zhao^{1,2,3,10}, Xiaofeng Liu^{1,2,3,11}, Xiangkun Lin^{1,2,3}, Zhilin Xia⁴,
Keqiang Qiu⁵, Dawei Li^{1,3}, He Gong^{1,6}, Yan Zhou^{1,6}, Jian Sun^{1,3}, Li Zhou⁷, Youen Jiang⁷,
Yaping Dai⁸, Jianda Shao^{1,3,9}

¹ *Laboratory of Thin Film Optics, Shanghai Institute of Optics and Fine Mechanics, Shanghai 201800, China*

² *Center of Materials Science and Optoelectronics Engineering, University of Chinese Academy of Sciences, Beijing 100049, China*

³ *Key Laboratory of Materials for High Power Laser, Chinese Academy of Sciences, Shanghai 201800, China*

⁴ *School of Materials Science and Engineering, Wuhan University of Technology, Wuhan, Hubei 430070, China*

⁵ *National Synchrotron Radiation Laboratory, University of Science and Technology of China, Hefei, Anhui 230029, China*

⁶ *School of Optical-Electrical and Computer Engineering, University of Shanghai for Science and Technology, Shanghai 200093, China*

⁷ *National Laboratory on High Power Laser and Physics, Shanghai Institute of Optics and Fine Mechanics, CAS, Shanghai, 201800, China*

⁸ *Research Center of Laser Fusion, China Academy of Engineering Physics, Mianyang, Sichuan 621900, China*

⁹ *Hangzhou Institute for Advanced Study, University of Chinese Academy of Sciences, Hangzhou 310024, China*

¹⁰ *yazhao@siom.ac.cn*

¹¹ *liuxiaofeng@siom.ac.cn*

Abstract Multilayer dielectric gratings (MLDGs) are crucial for pulse compression in picosecond-petawatt laser systems. Bulged nodular defects, embedded in coating stacks during multilayer deposition, influence the lithographic process and performance of the final

This peer-reviewed article has been accepted for publication but not yet copyedited or typeset, and so may be subject to change during the production process. The article is considered published and may be cited using its DOI.

This is an Open Access article, distributed under the terms of the Creative Commons Attribution licence (<https://creativecommons.org/licenses/by/4.0/>), which permits unrestricted re-use, distribution, and reproduction in any medium, provided the original work is properly cited.

10.1017/hpl.2023.74

29 MLDG products. In this study, the integration of nanosecond laser conditioning (NLC) into
30 different manufacturing stages of MLDG was proposed for the first time: on multilayer
31 dielectric films (MLDFs) and final grating products to improve laser-induced damage
32 performance. The results suggest that the remaining nodular ejection pits introduced by the
33 two protocols exhibit a high nanosecond-laser damage resistance, which remains stable
34 when the irradiated laser fluence is more than twice the nanosecond-laser-induced damage
35 threshold (nanosecond-LIDT) of the unconditioned MLDGs. Furthermore, the picosecond-
36 LIDT of the nodular ejection pit conditioned on the MLDFs was $\sim 40\%$ higher than that of
37 the nodular defects, and the loss of the grating structure surrounding the nodular defects was
38 avoided. Therefore, NLC is an effective strategy for improving the laser damage resistance
39 of MLDGs.

40 **Key words:** *Multilayer dielectric gratings; nanosecond laser conditioning; nodular defects;*
41 *laser-induced damage threshold; picosecond-petawatt laser systems*

42
43 Correspondence to: Yuan'an Zhao, Laboratory of Thin Film Optics, Shanghai Institute of Optics
44 and Fine Mechanics, Shanghai 201800, China. Email: yazhao@siom.ac.cn
45 Xiaofeng Liu, Laboratory of Thin Film Optics, Shanghai Institute of Optics and Fine Mechanics,
46 Shanghai 201800, China. Email: liuxiaofeng@siom.ac.cn

47 I. Introduction

48 High-energy petawatt laser systems (HPLSs) ^[1-4] have unparalleled application in inertial
49 confinement fusion ^[5], laboratory extreme physics research ^[6], and laser-accelerated particle beams
50 ^[7,8]. Chirped pulse amplification (CPA) ^[9,10] technology has been utilized to achieve ultra-high-
51 intensity pulse outputs in HPLSs. The laser-induced damage threshold (LIDT) of a multilayer
52 dielectric grating (MLDG), which is a key optical component of the CPA system, directly
53 determines the final output capacity of the entire system. Since MLDGs were proposed, the quest

54 for more robust MLDGs has promoted the investigation of their laser damage resistance
55 enhancement and laser-induced damage mechanisms.

56 The first investigations on LIDT enhancement of MLDGs were reported in 1996 [11].
57 Although some benefits were obtained by optimizing the ion-beam etching manufacturing process
58 [12], the electric-field intensity (EFI) enhancement introduced by the surface-relief grating structure
59 was unavoidable, and the LIDT exhibited a strong dependence on the EFI. Because the initial
60 damage of MLDGs induced by a ultrashort pulse is directly related to the EFI distribution [13,14],
61 theoretical optimization of the near field in MLDGs has become the focus of several studies [13-16].
62 The EFI enhancement can be decreased by increasing the incident angle [12] and using a thin pillar
63 profile [15]. Xie et al. [16] manufactured a rectangular MLDG profile to further reduce the EFI in the
64 grating pillar. In addition, surface contaminants, including photoresists, etch residues, and surface
65 debris, are well-known reasons for reducing the laser damage resistance [17-19]. Developing
66 advanced cleaning methods, such as dilute-buffered hydrofluoric acid solution cleaning [20] and
67 low-temperature chemical cleaning [21], can improve the laser damage resistance of MLDGs.
68 Recently, these contaminants have been shown to extend to a 50- to 80-nm layer below the surface
69 [22].

70 Efforts have been devoted to minimizing the peak EFI and reducing the subsurface
71 contamination produced during MLDG fabrication [22,23]. However, potential defects, especially
72 nodular defects in multilayer coating stacks [24], primarily limit the laser damage resistance of
73 MLDGs exposed to nanosecond- and picosecond-laser irradiation [25-29]. Moreover, the presence
74 of nodules results in the absence of a grating structure around the bulge area [30]. These factors
75 necessitate the removal of nodular defects. Based on the successful application of laser
76 conditioning in high reflectors and polarizers [31-38], we first propose removal of nodular defects in

77 MLDGs through nanosecond laser conditioning (NLC). Since the nodular defects are deposited
78 during the preparation of multilayer dielectric films (MLDFs), the appropriate process stage for
79 performing NLC needs to be identified. If NLC is performed before the surface-relief grating
80 structure is fabricated (on the MLDF), then the pits and scalding regions induced by the MLDF
81 conditioning may affect the subsequent lithography process. However, if the NLC is performed on
82 the final grating products, can the effect of nodule removal on the surface-relief grating structure
83 be tolerated?

84 In this study, two options for integrating NLC into the MLDG fabrication process were
85 introduced to remove nodular defects. The NLC was applied to the MLDFs (Protocol 1) and final
86 MLDGs (Protocol 2), as shown in Fig. 1 (b) and (c). We first investigated the effects of the nodular
87 ejection pits formed in these two protocols and simulated their electric-field distributions using the
88 finite element method (FEM). Subsequently, the morphological characteristics of the plasma-
89 scalding regions that appeared in the two protocols were compared. Finally, nanosecond- and
90 picosecond-laser raster scan damage tests were performed on the unconditioned and conditioned
91 MLDGs to evaluate the overall effects of these two conditioning protocols. A maximum
92 improvement of approximately 40 % was observed in the picosecond-LIDT of the MLDGs after
93 the removal of the nodular defects.

94 **II. Sample and experimental protocols**

95 MLDFs were deposited with alternating $\text{HfO}_2/\text{SiO}_2$ layers on a $50 \text{ mm} \times 50 \text{ mm} \times 1.5 \text{ mm}$ fused
96 silica substrate by electron beam evaporation. The basic stack formula ^[39] of the multilayer film is
97 based on $(\text{H}2\text{L})^k$, where H and L represent quarter-wave optical thickness layers of HfO_2 and SiO_2
98 respectively. Subsequently, the MLDFs were subjected to photoresist spin-coating, exposure,
99 photoresist development, etching, and cleaning to obtain the final MLDGs. The MLDGs were
100 designed with a groove density of 1740 lines/mm, which could provide a -1st-order diffraction

101 efficiency of more than 97 % at an incidence of 67° in a transverse electric (TE) polarized laser
102 with a wavelength of 1064 nm ^[30].

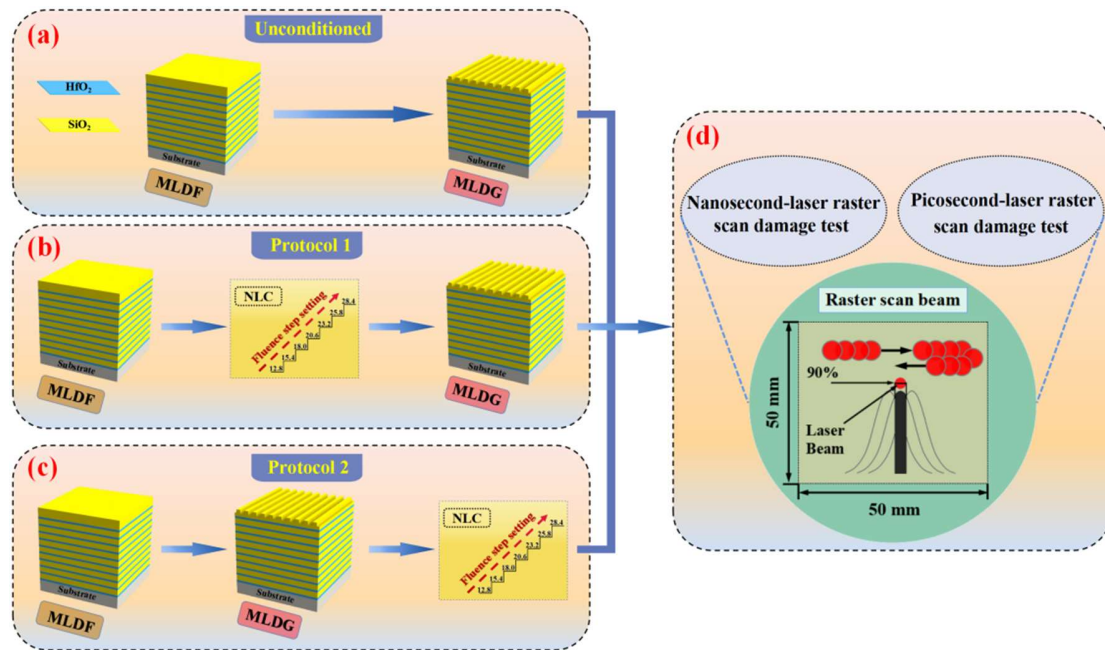
103 The NLC process was introduced to the MLDF (Protocol 1) and final MLDG (Protocol 2), as
104 shown in Fig. 1 (b) and (c), respectively. Subsequently, nanosecond- and picosecond-laser damage
105 experiments were performed on the unconditioned and conditioned MLDGs to evaluate and
106 compare their laser damage resistances. The raster scanning method ^[30] was applied in the NLC
107 and laser damage experiments, and the distance between the neighboring test sites was equal to
108 the diameter of the beam at 90 % of the peak fluence, as shown in Fig. 1 (d). The laser scanning
109 speed was set to ~ 8.3 mm/s with a laser repetition rate of 30 Hz.

110 The NLC and nanosecond-laser experiments were performed using a 1064 nm Nd:YAG laser
111 at an incidence of 67° in the TE polarization mode as described in ^[30]. The nanosecond-laser pulse
112 width was ~ 8.0 ns, and the waist radius of the Gaussian beam at a normal incidence was ~ 0.6 mm.
113 During the NLC process, the fluence of the incident laser was gradually increased from 12.8 to
114 28.4 J/cm^2 , which was higher than that of the nanosecond-LIDTs of the samples. This was expected
115 to remove nodular defects effectively and cause a negligible and benign damage.

116 The picosecond-laser damage apparatus is described in ^[40,41]. The incident laser was operated
117 at a central wavelength of 1053 nm with an incident angle of 67° in the TE polarization mode. The
118 picosecond-laser pulse width was ~ 8.6 ps, and the waist radius of the focused beam was ~ 48.9
119 μm . During the picosecond-laser damage experiment, the regions where the nodular defects and
120 nodular ejection pits were generated by Protocols 1 and 2 were raster-scanned for comparison.

121 LIDT is defined as the maximum fluence at which no damage occurs. The laser fluence used
122 in this study was provided as the beam normal. The damage density measured as a function of the

123 laser fluence was defined as the number of damage sites per scanning area (1 cm^2 for the raster
 124 scan in the final nanosecond-laser damage tests).



125
 126 Fig. 1. Schematic representation of the nanosecond- and picosecond-laser damage tests performed
 127 on three types of MLDG samples: (a) Unconditioned MLDG, (b) MLDF conditioning, and (c)
 128 MLDG conditioning. (d) Schematic of the raster scan damage tests.

129 Optical microscopy (OM, Olympus BX53M) and focused ion beam scanning electron
 130 microscopy (FIB-SEM, Zeiss Auriga) were used to characterize the morphological evolution after
 131 conditioning, photoresist spin-coating, and cleaning in Protocol 1 as well as to evaluate the effects
 132 of the byproducts of the two protocols on the morphology of the grating surface. Finally, the laser
 133 damage resistance of the MLDGs conditioned by these two protocols were compared under a
 134 gradually increasing incident laser fluence.

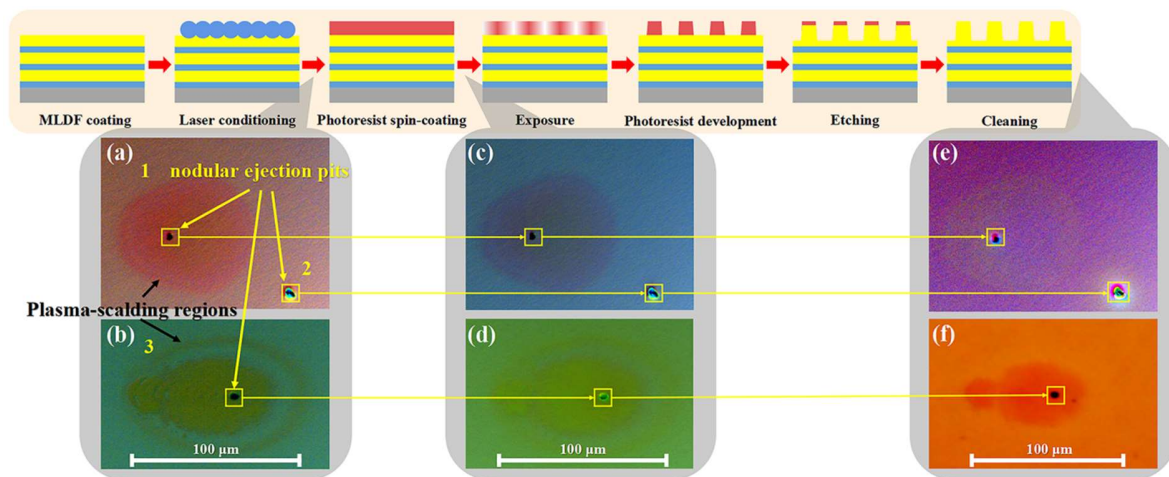
135 III. Morphological comparison and analysis

136 NLC with nodular defects introduced two typical byproducts (nodular ejection pits and plasma-
 137 scalding regions) in the final MLDGs. We first tracked the morphological characteristics of the

138 nodular ejection pits generated in Protocol 1 at different preparation stages. The effects of the two
 139 byproducts generated by these two protocols on the surface morphology of the MLDG were
 140 analyzed and compared.

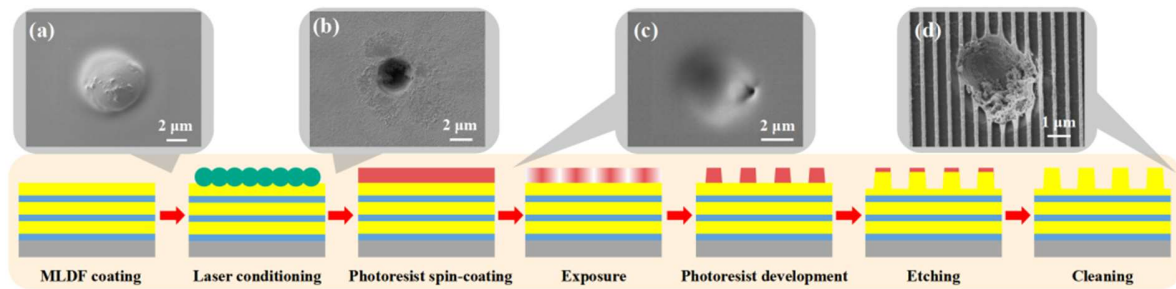
141 3.1. Nodular ejection pits

142 Fig. 2 shows the surface morphologies of the nodular ejection regions after the MLDF conditioning,
 143 spin-coating, and MLDG cleaning in Protocol 1. The nodular ejection pits marked as 1 and 3 in
 144 Fig. 2 (a) and (b), respectively, are accompanied by discolored plasma scalds, whereas the position
 145 marked as 2 in Fig. 2 (a) represents a nodular ejection pit without a scald. Fig. 2 (c)–(f) show that
 146 the nodular ejection pits and plasma scalds remain the same after the photoresist spin-coating and
 147 MLDG cleaning processes, respectively. Thus, the morphological modifications introduced by
 148 Protocol 1 exhibit replication characteristics at the subsequent process stages, and OM analyses
 149 reveal that these replication characteristics do not seem to affect the subsequent preparation
 150 process of the MLDG.



151
 152 Fig. 2. OM images of the nodular ejection pits and plasma scalds originating from Protocol 1. (a) and (b)
 153 Before photoresist spin-coating after MLDF conditioning. (c) and (d) After photoresist spin-coating. (e)
 154 and (f) After MLDG cleaning.

155 Further morphological characterization was performed using SEM. Fig. 3 (a) shows the
 156 typical surface morphology of a nodular defect in the MLDF, which has an evident bulge structure.
 157 Fig. 3 (b)–(d) display the morphological characteristics corresponding to the nodular ejection pits
 158 after the MLDF conditioning, photoresist spin-coating, and MLDG cleaning, respectively. The
 159 results indicate that the pit is filled with photoresist after the spin-coating, and the multilayer
 160 structure in the pit cannot be observed, as shown in Fig. 3 (c). After cleaning, the internal structure
 161 of the pit was reproduced, and the grating relief structure was etched in the area around the pit, as
 162 shown in Fig. 3 (d).



163
 164 Fig. 3. SEM images of the nodular defect and ejection pits at the different MLDG fabrication stages. (a) Typical
 165 bulged nodular defect in the MLDF, and (b)–(d) morphologies of the nodular ejection pits after the MLDF
 166 conditioning, photoresist spin-coating, and grating cleaning, respectively.

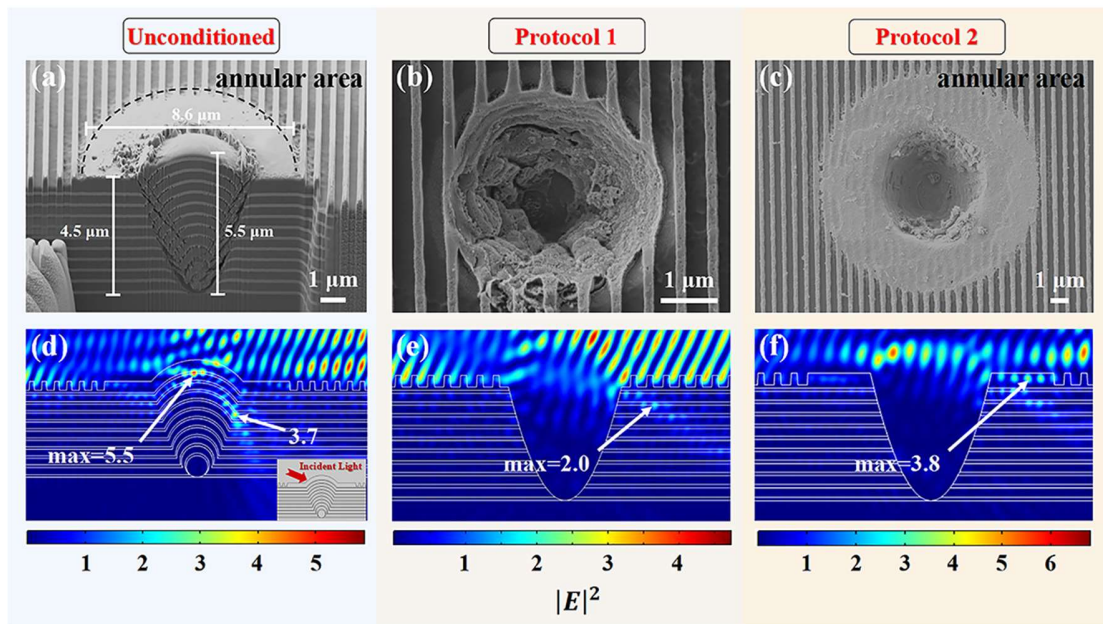
167 The bulging nodular defect results in the absence of grating structures in the surrounding
 168 annular area, as shown in Fig. 3 (a), because of the presence of nodular defects, which affect the
 169 distribution of the surrounding exposure field during the exposure stage of the MLDG fabrication.
 170 After removing the nodule, as in Protocol 1, the nodular ejection pit in the MLDG exhibits a small
 171 affected area with a tightly surrounding grating structure, as shown in Fig. 4 (b). However, Protocol
 172 2 cannot prevent the disappearance of grating structures around the nodular ejection pit, as shown
 173 in Fig. 4 (c). The square of EFI enhancement ($|E^2|$) distributions of the nodular defects and nodular
 174 ejection pits were simulated using the FEM. A two-dimensional simulation model with periodic
 175 boundaries on the left- and right-hand sides was used to reduce the computation. The simulation

176 domain was 100 μm wide and 7.5 μm high for nodular defects and nodular pits initiating from the
 177 1 μm seeds. The geometry of the nodular defect can be expressed as: $D = \text{sqrt}(4dt)$ ^[42], where
 178 D is the nodule diameter, d is the diameter of the nodular seed, and t is the seed depth. Table 1
 179 lists the model parameters used in the calculations.

180 **Table 1. Model parameters used in the calculations.**

Parameter	d	t	n_L	n_H	Wavelength	Incidence	Polarization
Value	1 μm	4.5 μm	1.453	1.962	1064 nm	67°	TE

181 Note: n_L and n_H represent the refractive indices of SiO_2 and HfO_2 , respectively.
 182 The parabolic structure generated by the nodular ejection is reset as an air domain, and only
 183 the annular areas around the pits generated by Protocols 1 and 2 are different. Fig. 3 (d) shows the
 184 $|E^2|$ distributions of the bulged nodular defect, and Fig. 4 (e) and (f) depict the two typical nodular
 185 ejection pits caused by Protocols 1 and 2, respectively. The maximum $|E^2|$ of the nodular defect
 186 (= 5.5) is observed in the dome film at the top of the defect, as shown in Fig. 3 (d). In addition, a
 187 strong $|E^2|$ (= 3.7) is detected at the right boundary between the nodule and the holonomic layer.
 188 For the nodular ejection pits, the maximum $|E^2|$ in the pits generated by Protocols 1 and 2 decrease
 189 to 2.0 and 3.8, respectively, as shown in Fig. 3 (e) and (f). This result indicates that the laser
 190 damage resistance of the nodular ejection pits seems to be higher than that of the nodular defects,
 191 especially that of the pits generated in Protocol 1.



192

193 Fig. 4. (a) Typical cross-sectional morphology of a nodular defect in the unconditioned MLDG.

194 (b) and (c) SEM images of the typical nodular ejection pits caused by Protocols 1 and 2,

195 respectively. (d)–(f) Simulated $|E|^2$ distributions corresponding to the morphological structures in

196

(a)–(c), respectively.

197 3.2. Plasma-scalding regions

198 The effects of the plasma scalds, induced by the two protocols, on the final grating structure were

199 evaluated. Fig. 5 (a) presents the typical morphology of a plasma-scalding region, with two

200 elliptical structures and a bright nodular ejection pit, induced by Protocol 1. Six positions outside

201 the center of the pit were selected for comparison. Fig. 55 (b)–(g) present the local magnified

202 images of the positions marked by rectangles in Fig. 55 (a). For comparison, the pristine surface is

203 also displayed in Fig. 55 (g), which shows a clear boundary between the pillars and grooves. In the

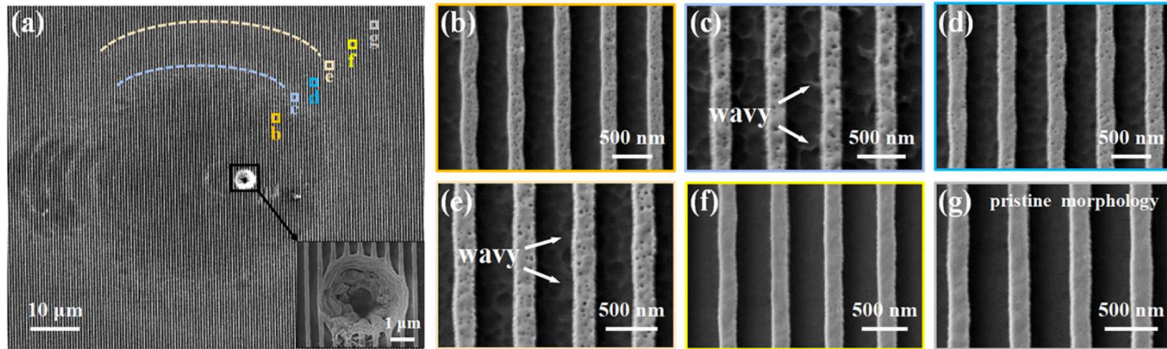
204 elliptical plasma-scalding region, some molten holes are visible on the surface of the pillars,

205 particularly at the edges of the two ellipses marked as c and e. In addition, the grating grooves,

206 shown in Fig. 55 (c) and (e), exhibit some “wavy” features possibly due to the relatively severe

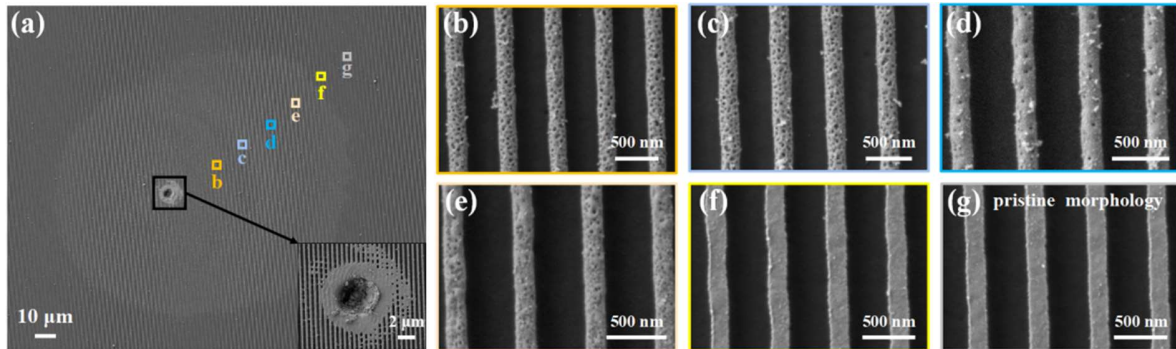
207 scald; by contrast, this feature is not noticeable in the grating grooves at the positions marked as b

208 and d. At the outside point f, which is near the outer edge of the plasma-scalding region, the pillars
 209 and grooves are not affected, and the surface morphology is consistent with that of the primitive
 210 surface shown in Fig. 5 (g).



211
 212 Fig. 5. (a) SEM image of the plasma-scalding region induced by the NLC in Protocol 1; the inset image shows a local
 213 magnified view of the nodular ejection pit. (b)–(g) Local magnified SEM images of the positions marked by
 214 rectangles (in color) in Fig. 5 (a).

215 The typical morphological characteristics of the bright plasma-scalding region with a nodular
 216 ejection pit induced by Protocol 2 are shown in Fig. 6 (a). Fig. 6 (b)–(g) show the local magnified
 217 SEM images of the six positions marked by rectangles (in color) in Fig. 6 (a). However, in contrast
 218 to the morphology induced by Protocol 1, in the case of Protocol 2, more molten holes are
 219 concentrated on the pillar surface, especially at the positions near the ejection pit marked by b and
 220 c. Furthermore, although many ejection residues also adhere to the surface of the grating pillars,
 221 the grating grooves are not modified, and their surfaces are smooth. At position f outside the
 222 scalding region, the morphological characteristics of the pillars are almost the same as those of the
 223 pristine surface of the MLDGs, as shown in Fig. 6 (f) and (g), similar to by Protocol 1.



224

225

226

227

Fig. 6. (a) SEM image of the plasma-scalding region induced by the NLC in Protocol 2; the inset image indicates the local magnified view of the central nodular ejection pit. (b)–(g) Local magnified SEM images of the positions marked by rectangles (in color) in Fig. 56 (a).

228

IV. Laser damage results and discussion

229

4.1. Comparison of nanosecond-laser damage performances

230

4.1.1. LIDT and damage density

231

The nanosecond-LIDTs and damage densities of the unconditioned and conditioned MLDGs are

232

shown in **Error! Reference source not found.**7 (a) and (b), respectively. The LIDT of the MLDGs

233

conditioned by Protocol 1 and that of the unconditioned MLDGs are almost the same (15.4 J/cm^2),

234

whereas that of the MLDGs conditioned by Protocol 2 is higher (18.0 J/cm^2). The damage density

235

is calculated as the number of damaged sites in an area of 1 cm^2 . Overall, the damage densities of

236

the three types of samples increase with the laser fluence for different slopes. The damage densities

237

of the MLDGs conditioned using Protocols 1 and 2 decrease, especially that of the latter. Fig. 7 (b)

238

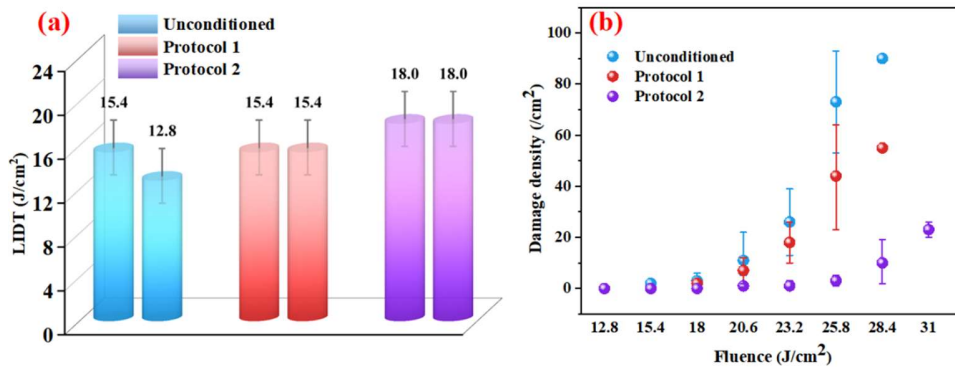
shows that when the irradiated laser fluence reaches 25.8 J/cm^2 , the damage density of the

239

unconditioned MLDGs is $73 /\text{cm}^2$, whereas those of the MLDGs conditioned by Protocols 1 and

240

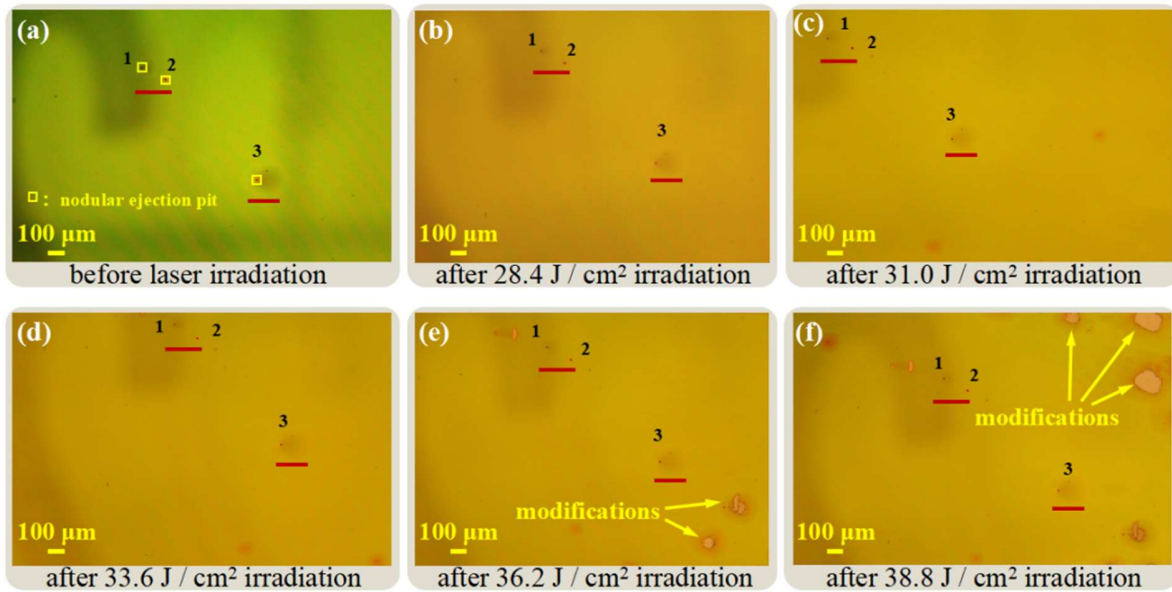
2 are 50 and $3 /\text{cm}^2$, respectively.



241
 242 Fig. 7. (a) LIDT results of the nanosecond-laser raster scan, the two thresholds represent the
 243 results of two different test samples. (b) Damage density versus laser fluence (only the damage
 244 points that appear in the nanosecond-laser damage test process are counted as damage).

245 4.1.2. Damage resistance of nodular ejection pits

246 The nanosecond-laser damage resistance of the nodular ejection pits induced by the two NLC
 247 protocols was further evaluated. Fig. 8 (a) shows the pristine morphological modifications of the
 248 three nodular ejection pits caused by the NLC in Protocol 1. The morphological evolution of the
 249 pits was characterized under gradually increasing incident laser fluence, and the corresponding
 250 results are shown in Fig. 8 (b)–(f). Even if new severely damaged modifications appear in the
 251 scanning area with no observable defects, the nodular ejection pit areas (marked by red lines)
 252 remain highly resistant to higher-fluence irradiation. This observation suggests that the nodular
 253 ejection pits induced by the NLC in Protocol 1 are stable and do not cause any catastrophic damage,
 254 even at a fluence of $38.8 \text{ J}/\text{cm}^2$, as shown in Fig. 8 (f).



255

256

257

258

259

Fig. 8. (a) OM image showing the pristine morphological modifications of the three nodular ejection pits induced by the NLC in Protocol 1. (b)–(f) OM images showing the morphologies of the ejection pit areas irradiated by gradually increasing nanosecond-laser fluences; here, the red lines represent the nodular ejection pits on the MLDG.

260

261

262

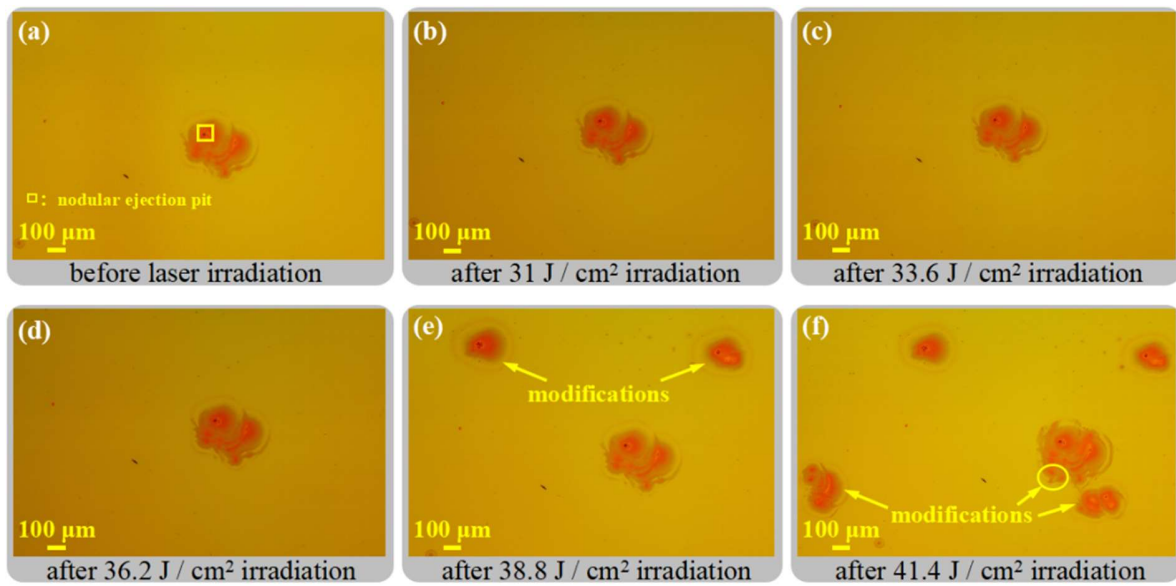
263

264

265

266

The morphological changes in a nodular ejection pit caused by the NLC in Protocol 2 were also tracked under gradually increasing incident laser fluences, and the results are displayed in Fig. 9 (a) – (f). Similar to the pits in Protocol 1, the nodular ejection pit in Protocol 2 is highly stable under the irradiation of a laser fluence of 38.8 J/cm². When the laser fluence reaches 41.4 J/cm², noticeable modifications appear in the plasma-scalding area, as shown in Fig. 9 (f). Both the pits caused by the two NLC protocols can withstand a laser fluence of 38.8 J/cm², which is higher than twice the LIDTs of the unconditioned MLDGs (15.4 and 12.8 J/cm²) shown in Fig. 7 (a).



267

268 Fig. 9. (a) OM image showing the pristine morphological modifications of a nodular ejection pit

269 induced by the NLC in Protocol 2. (b)–(f) Ejection pit region irradiated by gradually increasing

270

nanosecond-laser fluences.

271

4.2. Comparison of picosecond-laser damage performances

272

4.2.1. LIDT and damage morphology

273

The picosecond-laser damage results of the nodular defects and nodular ejection pits caused by the

274

NLC in Protocols 1 and 2 are displayed in Fig. 10. The LIDT of the nodular defects is 2.0 J/cm²,

275

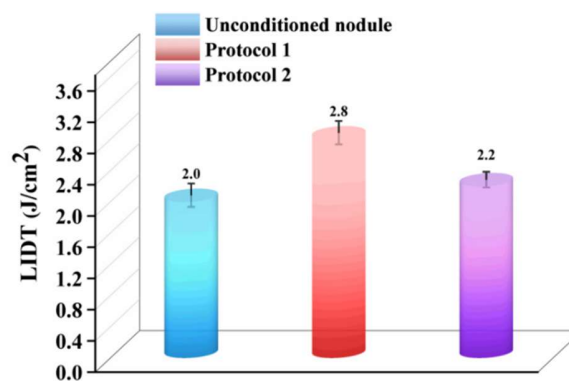
which is the lowest among those of the three sites. The LIDTs for the areas of the nodular ejection

276

pits produced by Protocols 1 and 2 are 2.8 and 2.2 J/cm², respectively, which are ~40 % and ~10 %

277

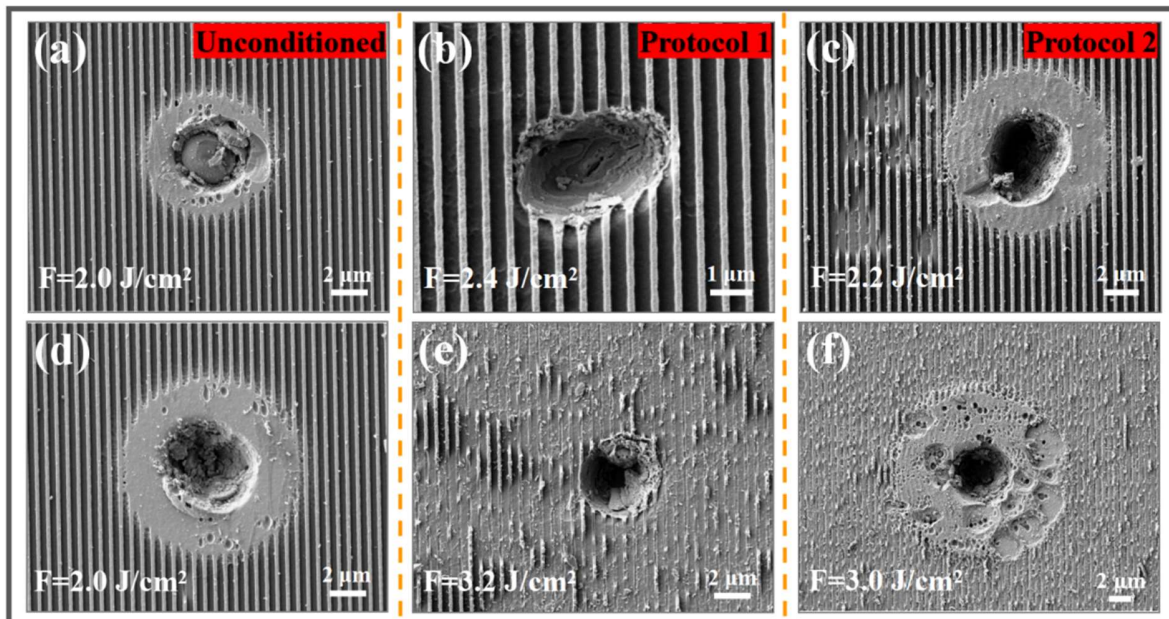
higher than those of the nodular defects.



278

279 Fig. 10. Picosecond-LIDTs of the unconditioned nodule and nodular ejection pits conditioned by Protocols 1 and 2.

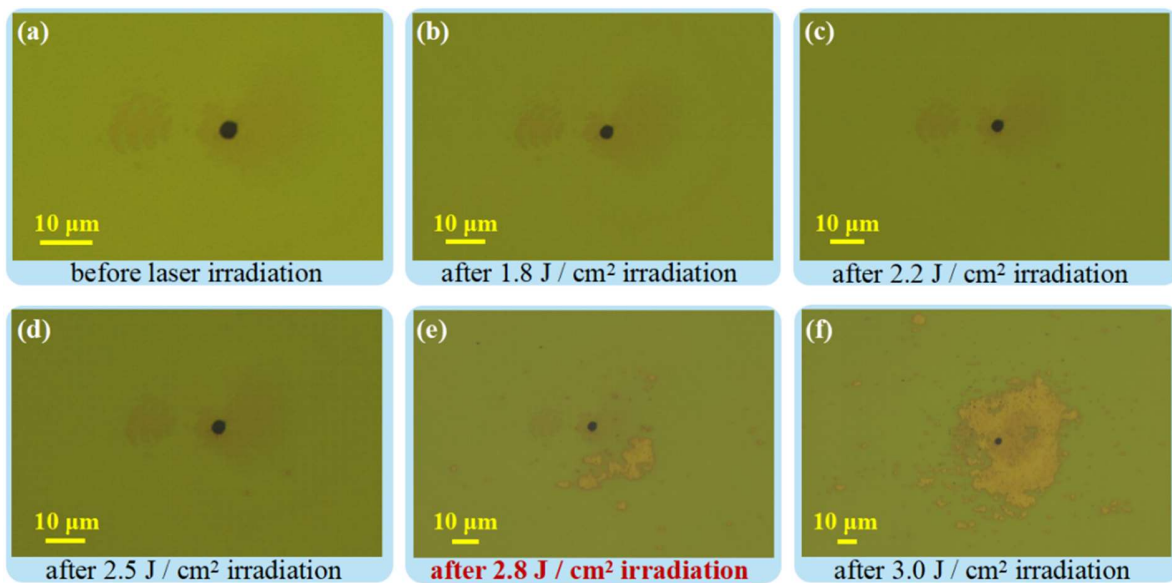
280 The nodular defects are partially or completely ejected under a low laser fluence of 2.0 J/cm^2 ,
 281 while the surrounding grating pillars remain intact, as shown in Fig. 11 (a) and (d). This result
 282 indicates that these unstable nodular defects limit the LIDT of the MLDG. Fig. 11 (b) and (e) show
 283 that the nodular ejection pit in Protocol 1 remains intact under a laser fluence of 2.4 J/cm^2 as well
 284 as remains stable under a laser fluence of 3.2 J/cm^2 , while a catastrophic damage occurs in the
 285 surrounding pillars. The pillars near the ejection pit caused by Protocol 2 are more susceptible to
 286 damage than those caused by Protocol 1 and first fractured under a fluence of 2.2 J/cm^2 , as shown
 287 in Fig. 11 (c). Fig. 11 (f) reveals that a laser fluence of 3.0 J/cm^2 damages almost all the pillars,
 288 and this damage may be attributed to the melting modification of the pillars in the plasma-scalding
 289 region, as shown in Fig. 6 (b) and (c).



290
 291 Fig. 11. Typical morphological characteristics of the different test areas induced during the picosecond-laser damage
 292 test. (a) and (d) Unconditioned nodular defects. (b) and (e) Nodular ejection pits caused by Protocol 1. (c) and (f)
 293 Nodular ejection pits caused by Protocol 2 (where F denotes the incident laser fluence).

294 4.2.2. Damage resistance of nodular ejection pits

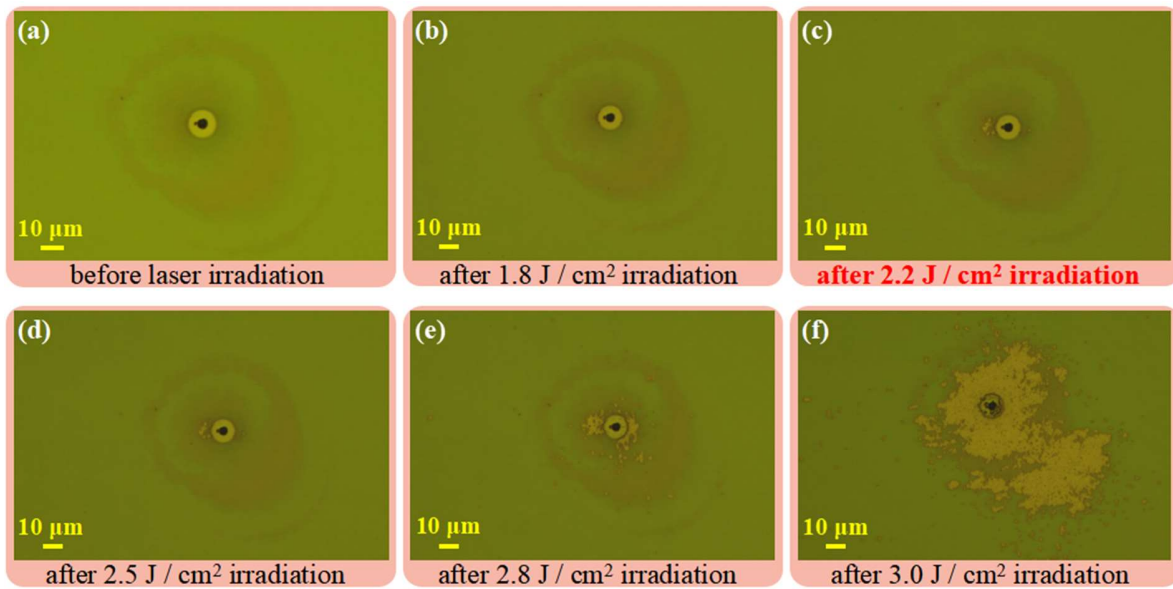
295 The picosecond-laser damage resistance of the two types of nodular ejection pits was evaluated by
 296 gradually increasing the laser fluence. Fig. 12 (b) – (f) show the morphological evolution of the
 297 nodular ejection pit in the case of Protocol 1. When the laser fluence is 2.8 J/cm^2 , the damage first
 298 occurs in the grating pillar area near the ejection pit, as shown in Fig. 12 (e). As the laser fluence
 299 increases to 3.0 J/cm^2 , the initial damaged area surrounding the ejection pit expands further;
 300 however, the ejection pit remains stable, as shown in Fig. 12 (f).



301 Fig. 12. (a) OM image showing the pristine morphological modification of a nodular ejection pit in Protocol 1. (b)–
 302 (f) OM images showing the morphologies of the ejection pit area irradiated by gradually increasing the
 303 picosecond-laser fluences.
 304

305 Fig. 13 (a) shows an OM image of a pristine nodular ejection pit with an annular plasma-
 306 scalding area caused by Protocol 2. The morphological evolution of the pit irradiated by
 307 gradually increasing the picosecond-laser fluence is shown in Fig. 13 (b) – (f). Evidently,
 308 the damage first occurs in the plasma-scalding region on the left side of the ejection pit at a low
 309 laser fluence of 2.2 J/cm^2 , as shown in Fig. 13 (c). As the incident laser fluence is increased, the
 310 damaged area gradually expands. When the laser fluence reaches 3.0 J/cm^2 , almost the entire

311 plasma-scalding region is catastrophically damaged, which may be caused by a more serious
 312 modification of the region during the NLC process.



313
 314 Fig. 13. (a) OM image showing the pristine morphological modification of a nodular ejection pit
 315 in Protocol 2. (b)–(f) OM images showing the morphologies of the ejection pit area irradiated by
 316 gradually increasing picosecond-laser fluences.

317 V. Conclusion

318 In this study, NLC, an effective method for removing nodular defects, was integrated into the
 319 different MLDG fabrication stages, i.e., after the MLDF coating (Protocol 1) and cleaning
 320 (Protocol 2). Subsequently, nanosecond- and picosecond-laser raster scan damage tests were
 321 performed on the unconditioned and conditioned MLDGs for comparison.

322 Following the MLDF conditioning, the modifications caused by the nodular ejection pit and
 323 plasma scald exhibited morphological replication after the photoresist spin-coating and cleaning
 324 of the MLDG. Unlike bulging nodular defects, the ejection pits did not eliminate the surrounding
 325 grating structure. In addition, the remaining nodular ejection pits introduced by the two protocols

326 exhibited a high nanosecond-laser stability and remained stable even when the irradiated laser
327 fluence was more than twice the nanosecond-LIDTs of the unconditioned MLDGs. The
328 picosecond-LIDT of the nodular ejection pits produced by the MLDF conditioning was ~40 %
329 higher than that of the nodular defects, whereas the LIDT of the nodular ejection pit produced by
330 the MLDG conditioning increased by only ~10 % owing to the melting modification of the plasma-
331 scalding region around the pit during the NLC process. Both the protocols can remove nodular
332 defects to improve the laser damage performance of MLDGs.

333 Laser conditioning performed using nanosecond pulses are universal and can be easily
334 integrated, because a vacuum environment to prevent the nonlinear self-focusing in air, which
335 occurs under the picosecond regime, is not required. Consequently, the NLC can be applied to
336 large-aperture gratings to improve their laser damage resistance.

337 **Acknowledgments**

338 This research was supported by the National Key R&D Program of China (2018YFE0115900),
339 the Key Foreign Cooperation Projects of Bureau of International Cooperation of Chinese
340 Academy of Sciences (Grant No. 181231KYSB20210001), and the Strategic Priority Research
341 Program of Chinese Academy of Sciences (Grant No.XDA25020314). The authors would like
342 to express their gratitude to Yun Cui, Jialong Gu, Lili Liu, Ziyuan Xu and Fanyu Kong from
343 the Shanghai Institute of Optics and Fine Mechanics for their help with the SEM observation,
344 laser-induced damage tests and grating preparation.

345 **References**

- 346 1. M. D. Perry, D. Pennington, B. C. Stuart, G. Tietbohl, J. A. Britten, C. Brown, S. Herman,
347 B. Golick, M. Kartz, J. Miller, H. T. Powell, M. Vergino, and V. Yanovsky, "Petawatt laser
348 pulses," *Opt. Lett.* 24(3), 160-162 (1999).

- 349 2. L. J. Waxer, D. N. Maywar, J. H. Kelly, T. J. Kessler, B. E. Kruschwitz, S. J. Loucks, R.
350 L. McCrory, D. D. Meyerhofer, S. F. B. Morse, C. Stoeckl, and J. D. Zuegel, "High-energy
351 petawatt capability for the OMEGA laser," *Opt. Photonics News* 16(7), 30-36 (2005).
- 352 3. C. Radier, O. Chalus, M. Charbonneau, S. Thambirajah, G. Deschamps, S. David, J. Barbe,
353 E. Etter, G. Matras, S. Ricaud, V. Leroux, C. Richards, F. Lureau, A. Baleanu, R. Banici,
354 A. Gradinariu, C. Caldararu, C. Capiteanu, A. Naziru, B. Diaconescu, V. Iancu, R. Dabu,
355 D. Ursescu, I. Dancus, C. A. Ur, K. A. Tanaka, and N. V. Zamfir, "10 PW peak power
356 femtosecond laser pulses at ELI-NP," *High Power Laser Sci. Eng.* 10(3), e21 (2022).
- 357 4. N. Blanchot, G. Behar, T. Berthier, B. Busserole, C. Chappuis, C. Damiens-Dupont, P.
358 Garcia, F. Granet, C. Grosset-Grange, J. P. Goossens, L. Hilsz, F. Laborde, T. Lacombe,
359 F. Lanieste, E. Lavastre, J. Luce, F. Macias, E. Mazataud, J. L. Miquel, J. Neauport, S.
360 Noailles, P. Patelli, E. Perrot-Minot, C. Present, D. Raffestin, B. Remy, C. Rouyer, and D.
361 Valla, "Overview of PETAL, the multi-Petawatt project in the LMJ facility," in *Eighth-*
362 *International-Conference-on-Inertial-Fusion-Sciences-and-Applications (IFSA, 2011),*
363 *paper 07001 (2013).*
- 364 5. R. Tommasini, O. L. Landen, L. B. Hopkins, S. P. Hatchett, D. H. Kalantar, W. W. Hsing,
365 D. A. Alessi, S. L. Ayers, S. D. Bhandarkar, M. W. Bowers, D. K. Bradley, A. D. Conder,
366 J. M. Di Nicola, P. Di Nicola, L. Divol, D. Fittinghoff, G. Gururangan, G. N. Hall, M.
367 Hamamoto, D. R. Hargrove, E. P. Hartouni, J. E. Heebner, S. I. Herriot, M. R. Hermann,
368 J. P. Holder, D. M. Holunga, D. Homoelle, C. A. Iglesias, N. Izumi, A. J. Kemp, T. Kohut,
369 J. J. Kroll, K. LaFortune, J. K. Lawson, R. Lowe-Webb, A. J. MacKinnon, D. Martinez,
370 N. D. Masters, M. P. Mauldin, J. Milovich, A. Nikroo, J. K. Okui, J. Park, M. Prantil, L. J.
371 Pelz, M. Schoff, R. Sigurdsson, P. L. Volegov, S. Vonhof, T. L. Zobrist, R. J. Wallace, C.
372 F. Walters, P. Wegner, C. Widmayer, W. H. Williams, K. Youngblood, M. J. Edwards, and
373 M. C. Herrmann, "Time-resolved fuel density profiles of the stagnation phase of indirect-
374 drive inertial confinement implosions," *Phys. Rev. Lett.* 125(15), (2020).
- 375 6. S. P. Hatchett, C. G. Brown, T. E. Cowan, E. A. Henry, J. S. Johnson, M. H. Key, J. A.
376 Koch, A. B. Langdon, B. F. Lasinski, R. W. Lee, A. J. Mackinnon, D. M. Pennington, M.
377 D. Perry, T. W. Phillips, M. Roth, T. C. Sangster, M. S. Singh, R. A. Snavely, M. A. Stoyer,
378 S. C. Wilks, and K. Yasuike, "Electron, photon, and ion beams from the relativistic

- 379 interaction of Petawatt laser pulses with solid targets,” *Phys. Plasmas* 7(5), 2076-2082
380 (2000).
- 381 7. A. X. Li, C. Y. Qin, H. Zhang, S. Li, L. L. Fan, Q. S. Wang, T. J. Xu, N. W. Wang, L. H.
382 Yu, Y. Xu, Y. Q. Liu, C. Wang, X. L. Wang, Z. X. Zhang, X. Y. Liu, P. L. Bai, Z. B. Gan,
383 X. B. Zhang, X. B. Wang, C. Fan, Y. J. Sun, Y. H. Tang, B. Yao, X. Y. Liang, Y. X. Leng,
384 B. F. Shen, L. L. Ji, R. X. Li, and Z. Z. Xu, “Acceleration of 60 MeV proton beams in the
385 commissioning experiment of the SULF-10 PW laser,” *High Power Laser Sci. Eng.* 10(4),
386 e26 (2022).
- 387 8. H. Daido, M. Nishiuchi, and A. S. Pirozhkov, “Review of laser-driven ion sources and their
388 applications,” *Rep. Prog. Phys.* 75(5), 056401 (2012).
- 389 9. D. Strickland and G. Mourou, “Compression of amplified chirped optical pulses,” *Opt.*
390 *Commun.* 56(3), 219–221(1985).
- 391 10. Z. Chen, S. Zheng, X. Lu, X. Wang, Y. Cai, C. Wang, M. Zheng, Y. Ai, Y. Leng, S. Xu,
392 and D. Fan, “Forty-five terawatt vortex ultrashort laser pulses from a chirped-pulse
393 amplification system,” *High Power Laser Sci. Eng.* 10(5), e32 (2022).
- 394 11. B. C. Stuart, M. D. Feit, S. Herman, et al., “Optical ablation by high-power short-pulse
395 lasers,” *J Opt Soc Am B* 13, 459-468 (1996).
- 396 12. J. A. Britten, W. A. Molander, A. M. Komashko, et al., “Multilayer dielectric gratings for
397 petawatt-class laser systems,” *Proc. SPIE* 5273, 1-7 (2004).
- 398 13. J. Neauport, E. Lavastre, G. Razé, G. Dupuy, and F. Desserouer, “Effect of electric field
399 on laser induced damage threshold of multilayer dielectric gratings,” *Opt. Express* 15(19),
400 12508-12522 (2007).
- 401 14. N. Bonod and J. Néauport, “Optical performance and laser induced damage threshold
402 improvement of diffraction gratings used as compressors in ultra high intensity lasers,”
403 *Opt. Commun.* 260(2), 649–655 (2006).
- 404 15. J. Néauport, and N. Bonod, “Pulse compression gratings for the PETAL project: a review
405 of various technologies,” *Proc. SPIE* 7132, 71320D (2009).
- 406 16. L. Y. Xie, J. L. Zhang, Z. Y. Zhang, B. Ma, and X. B. Cheng, “Rectangular multilayer
407 dielectric gratings with broadband high diffraction efficiency and enhanced laser damage
408 resistance,” *Opt. Express* 29(2), 2669-2678 (2021).

- 409 17. B. Ashe, K. L. Marshall, C. Giacomini, A. L. Rigatti, T. J. Kessler, A. W. Schmid, J. B.
410 Oliver, J. Keck, and A. Kozlov, "Evaluation of cleaning methods for multilayer diffraction
411 gratings," Proc. SPIE 6403, 64030O (2006).
- 412 18. B. Ashe, K. L. Marshall, D. Mastrosimone, and C. McAtee, "Minimizing contamination to
413 multilayer dielectric diffraction gratings within a large vacuum system," Proc. SPIE 7069,
414 706902 (2008).
- 415 19. B. Ashe, C. Giacomini, G. Myhre, and A. W. Schmid, "Optimizing a cleaning process for
416 multilayer-dielectric- (MLD) diffraction gratings," Proc. SPIE 6720, 67200N (2007).
- 417 20. H. T. Nguyen, C. C. Larson, and J. A. Britten, "Improvement of laser damage resistance
418 and diffraction efficiency of multilayer dielectric diffraction gratings by HF etchback
419 linewidth tailoring," Proc. SPIE 7842, 78421H (2010).
- 420 21. H. P. Howard, A. F. Aiello, J. G. Dressler, N. R. Edwards, T. J. Kessler, A. A. Kozlov, I.
421 Manwaring, K. L. Marshall, J. B. Oliver, and S. Papernov, "Improving the performance of
422 high-laser-damage-threshold, multilayer dielectric pulse-compression gratings through
423 low-temperature chemical cleaning," Appl. Opt. 52(8), 1682-1692 (2013).
- 424 22. N. Liu, R. Dent, B. N. Hoffman, A. A. Kozlov, J. B. Oliver, A. L. Rigatti, T. J. Kessler, S.
425 G. Demos, and A. A. Shestopalov, "Manufacturing- induced contamination in common
426 multilayerdielectric gratings," Opt. Express 31(1), 714-726 (2023).
- 427 23. J. Néauport, N. Bonod, and S. Hocquet, "Recent progress in the development of pulse
428 compression gratings," Proc. SPIE 8190, 81900O (2011).
- 429 24. T. Liu, M. Zhu, W. Du, J. Shi, J. Sun, Y. Chai, and J. Shao, "A nodule dome removal
430 strategy to improve the laser-induced damage threshold of coatings," High Power Laser
431 Sci. Eng. 10(5), e30 (2022).
- 432 25. X. Zou, F. Y. Kong, Y. X. Jin, P. Chen, J. M. Chen, J. Xu, Y. L. Wang, Y. B. Zhang, and
433 J. D. Shao, "Influence of nodular defect size on metal dielectric mixed gratings for ultra-
434 short ultra-high intensity laser system," Opt. Mater. 91, 177-182 (2019).
- 435 26. D. A. Alessi, C. W. Carr, R. P. Hackel, R. A. Negres, K. Stanion, J. E. Fair, D. A. Cross,
436 J. Nissen, R. Luthi, G. Guss, J. A. Britten, W. H. Gourdin, and C. Haefner, "Picosecond
437 laser damage performance assessment of multilayer dielectric gratings in vacuum," Opt.
438 Express 23(12), 15532-15544 (2015).

- 439 27. J. Xu, X. Zou, J. M. Chen, Y. B. Zhang, Y. L. Wang, Y. X. Jin, F. Y. Kong, H. C. Cao, P.
440 Chen, and J. D. Shao, "Metal dielectric gratings with high femtosecond laser damage
441 threshold of twice as much as that of traditional gold gratings," *Opt. Lett.* 44, 2871-2874
442 (2019).
- 443 28. H. Liddell, "Enhancing the performance of multilayer-dielectric diffraction gratings
444 through cleaning process modifications and defect mitigation," PhD. Thesis (University of
445 Rochester, 2014).
- 446 29. I. Jovanovic, C. G. Brown, B. C. Stuart, et al., "Precision damage tests of multilayer
447 dielectric gratings for high-energy petawatt lasers," *Proc. SPIE* 5647, 34-42 (2005).
- 448 30. X. K. Lin, Y. A. Zhao, X. F. Liu, D. W. Li, K. Shuai, H. Ma, Y. C. Shao, J. Sun, K. Q. Qiu,
449 Y. Cui, Y. P. Dai, and J. D. Shao, "Damage characteristics of pulse compression grating
450 irradiated by nanosecond laser," *Opt. Mater. Express* 12(2), 643-652 (2022).
- 451 31. S. Xu, X. Yuan, Y. Wei, X. Xia, and X. Zu, "Effect of UV laser conditioning on fused
452 silica in vacuum," *Opt. Mater.* 31, 1013-1016 (2009).
- 453 32. M. Sahraee, H. R. Fallah, H. Zabolian, B. Moradi, and M. H. Mahmoodzade, "Influence
454 of laser conditioning on laser induced damage threshold of single layers of ZrO₂ with
455 various deposition conditions," *Opt. Spectrosc.* 118, 627-630 (2015).
- 456 33. C. J. Stolz, L. M. Sheehan, S. M. Maricle, S. Schwartz, M. R. Kozlowski, R. T. Jennings,
457 and J. Hue, "Laser conditioning methods in hafnia silica multilayer mirrors," *Proc. SPIE*
458 3264, 105-112 (1998).
- 459 34. M. Kozlowski, C. Wolfe, M. Staggs, and J. Campbell, "Large area laser conditioning of
460 dielectric thin film mirrors," *Proc. SPIE* 1438, 143811 (1998).
- 461 35. H. Bercegol, "What is laser conditioning: a review focused on dielectric multilayers," *Proc.*
462 *SPIE* 3578, 421-426 (1998).
- 463 36. Y. N. Zhao, T. Wang, D. W. Zhang, J. Shao, and Z. Fan, "Laser conditioning and multi-
464 shot laser damage accumulation effects of HfO₂/SiO₂ antireflective coatings," *Appl. Surf.*
465 *Sci.* 245(1-4), 335-339 (2005).
- 466 37. J. Liu, X. Li, Z. K. Yu, H. Cui, W. L. Zhang, M. P. Zhu, and K. Yi, "Effect of laser
467 conditioning on the LIDT of 532nm HfO₂/SiO₂ thin films reflectors," *Proc. SPIE* 8786,
468 87860Z (2013).

- 469 38. Y. Zhao, J. Shao, T. Wang, D. Zhang, S. Fan, J. Huang, W. Gao, and Z. Fan, “Laser
470 conditioning of dielectric oxide mirror coatings at 1064 nm,” *Proc. SPIE* 5774, 599–602
471 (2004).
- 472 39. X. K. Lin, Y. A. Zhao, X. F. Liu, D. W. Li, H. Ma, Y. C. Shao, K. Q. Qiu, J. Sun, F. Y.
473 Kong, M. P. Zhu, and J. D. Shao, “Nanosecond laser damage characteristics of multilayer
474 dielectric films and gratings,” *Proc. SPIE* 11912, 119120O (2021).
- 475 40. Y. Hao, M. Sun, S. Shi, X. Pan, Z. Zhu, X. Pang, and J. Zhu, “Comparison between intrinsic
476 and contaminant-induced damages of multilayer dielectric gratings,” *Proc. SPIE* 10339,
477 103390H (2017).
- 478 41. K. Shuai, X. Liu, Y. Zhao, K. Qiu, D. Li, H. Gong, J. Sun, L. Zhou, Y. Jiang, Y. Dai, J.
479 Shao, Z. Xia. “Multilayer dielectric grating pillar-removal damage induced by a
480 picosecond laser,” *High Power Laser Sci. Eng.* 10(6), e42 (2022).
- 481 42. X. Cheng, J. Zhang, T. Ding, Z. Wei, H. Li, and Z. Wang, “The effect of an electric field
482 on the thermomechanical damage of nodular defects in dielectric multilayer coatings
483 irradiated by nanosecond laser pulses,” *Light-Sci. Appl.* 2, e80 (2013).